

Special Issue

Towards Ideal Nanomaterials

Message from the Guest Editor

Various nanomaterials are widely used in numerous applications where their functional properties are determined by the monodispersity of their active elements, e.g. nanoparticles. Generating 'ideal nanomaterial' with monodisperse nanoobjects is an extremely important and challenging task. The process opposing generation of monodisperse nanoobjects is coarsening, or Ostwald ripening. This process forcing the nanosystem towards minimum of its surface energy results in broadening of the nanoobjects' size distribution. Fabrication routs for nanomaterials with narrow size distribution of similar nanoobjects, the ways of inhibiting the coarsening process, theoretical studies of coarsening in nanosystems – these are the topics of immediate interest for this Special issue.

Guest Editor

Dr. Victor M. Burlakov

Linacre College, Oxford University, St Cross Road, Oxford OX1 3JA, UK

Deadline for manuscript submissions

closed (30 June 2021)



Applied Sciences

an Open Access Journal
by MDPI

Impact Factor 2.5
CiteScore 5.5



mdpi.com/si/47795

Applied Sciences
Editorial Office
MDPI, Grosspeteranlage 5
4052 Basel, Switzerland
Tel: +41 61 683 77 34
appls@mdpi.com

mdpi.com/journal/

[appls](https://appls.mdpi.com)





Applied Sciences

an Open Access Journal
by MDPI

Impact Factor 2.5
CiteScore 5.5



[mdpi.com/journal/
applsci](https://mdpi.com/journal/applsci)



About the Journal

Message from the Editor-in-Chief

As the world of science becomes ever more specialized, researchers may lose themselves in the deep forest of the ever increasing number of subfields being created. This open access journal Applied Sciences has been started to link these subfields, so researchers can cut through the forest and see the surrounding, or quite distant fields and subfields to help develop his/her own research even further with the aid of this multi-dimensional network.

Editor-in-Chief

Prof. Dr. Giulio Nicola Cerullo
Dipartimento di Fisica, Politecnico di Milano, Piazza L. da Vinci 32,
20133 Milano, Italy

Author Benefits

Open Access:

free for readers, with article processing charges (APC) paid by authors or their institutions.

High Visibility:

indexed within Scopus, SCIE (Web of Science), Ei Compendex, Inspec, CAPlus / SciFinder, and other databases.

Journal Rank:

JCR - Q2 (Engineering, Multidisciplinary) / CiteScore - Q1 (General Engineering)